

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s): Budinger	
Application No.: 09/805,328	Group Art Unit: 3723
Filed: 3/13/2001	
Title: WINDOW PORTION WITH AN ADJUSTED RATE OF WEAR	Examiner: W. Berry, Jr.
Attorney Docket No.: 156US	

PRELIMINARY AMENDMENT UNDER 37 CFR 1.115

Assistant Commissioner for Patents
Washington, D.C. 20231

Dear Sir:

Please add to the application new claims 33-44 as set forth below, and cancel pending claims 1-32.

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33. An apparatus for polishing a wafer comprising:
a polishing pad having a surface and a first wear rate during polishing;
a window portion formed in the polishing pad and having a surface formed flush with the polishing pad surface; and
wherein the window portion has a second wear rate during polishing equal to or greater than the first wear rate so that the window surface remains flush with the polishing pad surface during polishing.
34. The apparatus of claim 33, wherein the second wear rate is 5% to 25% greater than the first wear rate.